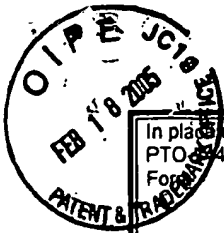


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OF

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Application Number	10/710,012
Filing Date	June 11, 2004
Applicant(s)	Chien-Chao Huang, et al.
Art Unit	2811 2812
Examiner Name	TBB Isabe
Attorney Docket Number	2001.1531 / 24061.439

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OTHER PRIOR ART

Examiner's Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article, title of the item, date, page(s), volume, issue number(s), publisher, city, country, where published
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Examiner
Signature

Date
Considered

9/18/05

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